

Chemical Compatibility of SWT Cartridges and Cartridge Seals

R = Resistant. No significant change was observed in flow rate or bubble point of the membrane following 48 hours exposure to the test fluid at 77°F (25°C).

LR = Limited Resistance. Moderate changes in physical properties or dimensions of the membrane were observed. The filter may be suitable for short term, noncritical use.

NR = Not Resistant. The membrane is basically unstable. In most cases, extensive shrinkage or swelling of the membrane occurs. The filter may gradually weaken or partially dissolve after extended exposure.

O = Insufficient Data. Testing on your own solution is recommended.

SWT's filter cartridges are designed and manufactured for their resistance to a wide range of chemical solutions.

The compatibility data presented in this chart provides results when cartridge materials are exposed to the chemical under static conditions for 48 hours at 77°F (25°C).

This information, while current, is intended for general guidance only. Conditions will vary with each application and users should carefully verify chemical compatibility.

If questions arise about compatibility in specific applications, please contact SWT.

	SWT Cartridges				SWT Cartridge Seals				
	System Guard	Spun PP Sediment	MP, MPE, XP	PM	Viton	Buna-N	EP	Silicone	Teflon
ACIDS									
Acetic Acid, 10%	R	R	R	R	LR	LR	R	R	R
Acetic Acid, 30%	R	R	R	R	NR	NR	LR	LR	R
Acetic Acid, 90%	R	R	R	R	NR	NR	LR	LR	R
Acetic Acid, Glacial	R	R	R	R	NR	NR	LR	LR	R
Chromic Acid, Concentrated	R	R	R	R	R	NR	NR	NR	R
Hydrochloric Acid, 6N	R	R	R	R	R	LR	LR	NR	R
Hydrochloric Acid, Concentrated	R	R	R	R	R	LR	LR	NR	R
Hydrofluoric Acid, 6N	R	R	R	R	R	NR	NR	NR	R
Nitric Acid, 6N	R	R	R	R	R	NR	NR	NR	R
Nitric Acid, Conc.	R	R	R	R	LR	NR	NR	NR	R
Phosphoric Acid, Concentrated	R	R	R	R	R	LR	R	NR	R
Sulfuric Acid, 6N	R	R	R	R	R	NR	LR	NR	R
Sulfuric Acid, Concentrated	R	R	R	R	R	NR	LR	NR	R
ALCOHOLS									
Amyl Alcohol	R	R	R	R	R	R	R	NR	R
Benzyl Alcohol, 3%	R	R	LR	R	R	R	R	R	R
Benzyl Alcohol, 100%	R	R	NR	R	R	NR	R	LR	R
Butanol	R	R	R	R	R	R	NR	NR	R
Ethanol	R	R	R	R	R	R	R	R	R
Isopropanol	R	R	R	R	R	R	R	R	R
Methanol	R	R	R	R	NR	R	R	R	R

Chemical Compatibility of SWT Cartridges and Cartridge Seals (Continued)

R = Resistant

LR = Limited Resistance

NR = Not Resistant

O = Insufficient Data

	SWT Cartridges				SWT Cartridge Seals				
	System Guard	Spun PP Sediment	MP, MPE, XP	PM	Viton	Buna-N	EP	Silicone	Teflon
BASES									
Ammonium Hydroxide, 3N	R	R	R	R	R	R	R	R	R
Ammonium Hydroxide, 6N	R	R	R	R	LR	NR	R	R	R
Potassium Hydroxide, 3N	R	R	R	R	R	R	R	LR	R
Sodium Hydroxide, 3N	R	R	R	R	R	R	R	R	R
Sodium Hydroxide, 6N	R	R	R	R	R	R	R	R	R
ESTERS									
Amyl Acetate	LR	LR	R	LR	NR	NR	LR	NR	R
Butyl Acetate	LR	LR	R	LR	NR	NR	R	NR	R
Cellosolve Acetate	R	R	R	R	NR	NR	R	NR	R
Diethyl Ether	LR	LR	NR	LR	NR	NR	NR	NR	R
Diisopropyl Ether	R	R	R	R	O	O	O	O	O
Dioxane	R	R	R	R	NR	NR	R	NR	R
Ethyl Acetate	LR	LR	NR	LR	NR	NR	LR	NR	R
Isopropyl Acetate	R	R	R	R	NR	NR	R	NR	R
Methyl Acetate	LR	LR	NR	LR	NR	NR	LR	NR	R
Tetrahydrofuran	LR	LR	R	LR	NR	NR	R	NR	R
GLYCOLS									
Ethylene Glycol	R	R	R	R	R	R	R	R	R
Glycerine	R	R	R	R	R	R	R	R	R
Propylene Glycol	R	R	R	R	R	R	R	R	R
AROMATIC HYDROCARBONS									
Benzene	NR	NR	LR	NR	R	NR	NR	NR	R
Toluene	NR	NR	LR	NR	R	NR	NR	NR	R
Xylene	NR	NR	LR	NR	R	NR	NR	NR	R
HALOGENATED HYDROCARBONS									
Carbon Tetrachloride	LR	LR	LR	LR	R	R	NR	NR	LR
Chloroform	LR	LR	NR	LR	R	R	NR	NR	LR
Chloroethene NU	LR	LR	NR	LR	R	NR	NR	NR	R
Dowclene WR	LR	LR	NR	LR	O	O	O	O	O
Freon TF	R	R	R	R	R	R	NR	R	R
Freon TMC	LR	LR	R	LR	O	O	O	O	O

